

Inventor: H. Daniel Dulman

Title: Radiation Patterning Tools, and Methods of Forming Radiation
Patterning Tools

Assignee: Micron Technology, Inc.

11046 U.S. PTO
10/072440
02/05/02


INFORMATION DISCLOSURE STATEMENT

PURSUANT TO 37 C.F.R. §§ 1.56, 1.97 AND 1.98

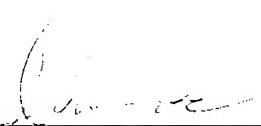
In compliance with 37 C.F.R. §§ 1.56, 1.97 and 1.98, the Examiner's attention is directed to the references listed on the attached Form PTO-1449 and copies of which are attached. No admission is made regarding whether all the submitted references are prior art.

Citation of these references is respectfully requested.

Respectfully submitted,

Date: 1/15/03

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Date: January 23, 2003 Inventor:


H. Daniel Dulman

Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-1829	SERIAL NO. Filed Herewith		
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)		APPLICANT H. Daniel Dulman					
		FILING DATE Filed Herewith		GROUP Unknown			
U.S. PATENT DOCUMENTS							
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA	5,208,125	05/93	Lowrey et al.			
	AB	5,217,830	06/93	Lowrey			
	AC	5,308,721	05/94	Garofalo et al.			
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						
	AL						
FOREIGN PATENT DOCUMENTS							
		Document Number	Date	Country	Class	Subclass	Translation
	AM						Yes
	AN						No
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
	AO		Kobayashi, S. et al., "Development of Simplified Process for KrF Excimer Half-Tone Mask with Chrome-Shielding Method". 19th Annual BACUS Sympos. on Photomask Technology, Monterey, CA, Sept. 1999, SPIE Vol. 3873, pp. 288-296.				
	AP		Kobayashi, S. et al., "Development of Simplified Process for KrF Excimer Half-Tone Mask with Chrome-Shielding Method (II)". 20th Annual BACUS Sympos. on Photomask Technology, Proceedings of SPIE Vol. 4186 (2001), pp. 801-809.				
	AQ		Lim, S. et al., "Application of Alternating Phase-Shifting Masks to Sub-Quarter Micron Contact Holes", SPIE Vol. 2726, Feb. 1996, pp. 516-523.				
	AR		Lim, S. et al., "Application of Alternating Phase-Shifting Masks to 200nm Contact Holes", SPIE Vol. 2884, July 1996, pp. 243-254.				
EXAMINER				DATE CONSIDERED			
<p>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant</p>							